A Novel Imide Synthesis via Silyl-Blocked Diamines

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Two groups^{1,2} have reported the synthesis of organosilylated polyamic acid resins from N,N'-bis-[trimethylsilyl]-diamines and their subsequent conversion to polyimides (Scheme A).

$$(CH_3)_3Si-NH-A-NH-Si(CH_3)_3 \xrightarrow{\text{dianhydride}/\\ THF, r.t.} \xrightarrow{\text{THF, r.t.}} \\ \begin{bmatrix} O & O \\ -NH-C & C \\ (CH_3)_3SiOOC & COOSi(CH_3)_3 \end{bmatrix}_n \xrightarrow{\text{heat}} \text{Polyimide} \\ + (CH_3)_3SiOH$$

Scheme A

Tabelle. Fortsetzung von S. 223

Analyse						Amide 5 ^b $[\alpha]_{578}^{22}$ (C = 1, Wasser)
C ₁₉ H ₂₅ O ₁₀ NS	ber,	C 49.67	H 5.49	N 3.05	S 6.98	+73.7
(459.5)	gef.	49.62	5.38	3.07	6.83	
C ₁₉ H ₂₄ O ₁₀ NSBr	ber.	C 42.39	H 4.49	N 2.60	S 5.96	+67.5
(538.4)	gef.	42.09	4.49	2.69	5.94	
$C_{18}H_{24}O_{10}N_2S$ (460.4)	ber. gef.	C 46.95 46.60	H 5.25 5.22	N 6.08 6.11	S 6.96 7.05	+80.4
C ₁₇ H ₂₃ O ₁₀ N ₃ S	ber.	C 44.25	H 5.02	N 9.11	S 6.95	+86.2°
(461.4)	gef.	44.08	4.99	8.99	6.75	
C ₁₇ H ₂₇ O ₁₁ NS	ber.	C 45.02	H 6.00	N 3.09	S 7.07	+91.7
(453.5)	gef.	44.68	5.94	3.10	7.12	

^c Umkristallisation aus 90%igen Äthanol; F: 168-169°.

 $C_{11}H_{17}O_7N_3S$ ber. C 39.40 H 5.11 N 12.53 S 9.56 (335.3) gef. 39.08 5.66 12.97 9.19

Efforts in these laboratories have resulted in the production of some trimethylsilyl-blocked diamines, which have been employed in a novel manner for the synthesis of polyimide model compounds. We have prepared three new silicon-

containing diimides by reacting 1 mol of bis-[N,N'-bis-(tri-methylsilyl)-4-aminophenyl]-disubstituted silanes² (1) with 2 mol of phthalic anhydride, thus establishing the reactivity of fully silylated diamines in imide formation (Scheme **B**).

$$(CH_{3})_{3}Si_{1} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

$$(CH_{3})_{3}Si_{2} N - Si_{1} - N Si(CH_{3})_{3} + 2$$

a $R^1 = R^2 = CH_3$ **b** $R^1 = CH_3$, $R^2 = C_6H_5$ **c** $R^1 = R^2 = C_6H_5$

Scheme B

Polymerization of the fully silylated diamines 1 to polyimides is currently under investigation. Our feeling is that the incorporation of additional trimethylsilyl groups during polymerization will engender increased solubility to the inter-

Table. Experimental Conditions and Results of the Synthesis of Compounds 2.

2 a	Solvent DMF	Reaction Conditions	Yield (%)	m. p. 235.5–238°	Elemental Analysis			Imide	I.R. ^c (cm ⁻¹) Silyl-R ¹ , R ²
					calc.	C 71.69 71.84	H 4.41 4.67	1781 ^d 1707 ^d	1236° 801 ^d
2 b	Diglyme	27 hr, 156–161°	61	255257.5°	found calc. found	C 74.45 74.57		1780 ^d 1710 ^d	1240, 780 ^d
2 c	DMF	24 hr, 130–141°	88ª	314.5–317°	calc. found	C 76.66 76.60	H 4.18 4.25	1784 ^d 1712 ^d	692 ^d

^aCrude yield. ^bUncorrected. ^cKBr pellet. ^dBroad. ^cWeak.

d Die optischen Drehwerte der sirupösen Verbindungen dürften mit einem geringen Fehler behaftet sein.

mediate and thus allow the production of a polyimide of higher molecular weight than can be achieved by conventional means.

$Bis-[N,N-bis-(trimethylsilyl)-4-amin ophenyl]-methylphenylsilane \ensuremath{\textbf{(1\,b)}}\xspace:$

To a stirred anhydrous ethereal solution of N,N-bis-[trimethyl-silyl]-4-bromoaniline (66 g, 0.209 mol) was added 2.25 N butyl-lithium (93 ml, 0.209 mol) at 0° under nitrogen. After a reaction period of 1 hr at room temperature, dichloromethylphenylsilane (20.0 g, 0.1045 mol) was added dropwise. The resultant solution was stirred overnight; after a 2 hr reflux, the lithium chloride was removed by filtration and the ether removed in vacuo. Distillation afforded 1b; yield: 36.7 g (59%); b.p. 202–204.5°/0.03 torr; $n^{24} = 1.5369$. A sample was recrystallized with difficulty from pentanes, m.p. 93–95°.

C₃₁H₅₂N₂Si₅ calc. C 62.77 H 8.84 (593.2) found 62.56 8.89

I.R. (neat): $v_{\text{max}} = 1246$, 830, 695 cm⁻¹; this spectrum showed no NH absorption.

 1 H-N.M.R. (CCl₄): δ = 7.27 (center of m, 13 H_{arom}), 0.84 (s, 3H, single methyl group on silicon), 0.14 ppm (s, 36H, trimethylsilyl protons).

N,N'-Bis-[4-aminophenylphthalimido]-methylphenylsilane (2b):

Bis-[N,N-bis-(trimethylsilyl)-4-aminophenyl]-methylphenylsilane (1b; 4.120 g, 0.0069 mol) and recrystallized phthalic anhydride (2.060 g, 0.0139 mol) in anhydrous diglyme (55 ml) under nitrogen were refluxed as shown in the Table, collecting 1.021 g (45%) of hexamethyldisiloxane. The purity of this material was judged to be $\sim 95\%$ by G.L.C. $n_D^{22} = 1.3776$ (Lit. reports $n_D^{25} = 1.3741$) as the reaction progressed. With cooling and the addition of a small amount of water, the diimide crystallized out of solution to give a crude, dry product, m.p. 239–242°. Recrystallization from pyridine/water gave pure 2b; yield: 2.39 g (61%); m.p. 255–257.5°.

The support of this research by the National Aeronautics and Space Administration, as well as generous supplies of silicon reagents from Dr. W. H. Daudt of Dow Corning Corporation, is gratefully acknowledged.

Received: November 13, 1972

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